

10-639,465

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)		APPLICANT YAMAZAKI, et al.	
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Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date
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GA	AB 6,319,840	11-2001	Costrini, et al.			
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GA	AM 11330463	11-1999	Japan			Yes No
GA	AN 2805924	9-2001	France			
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Examiner	George Goudreau	Date Considered 3-06-1